

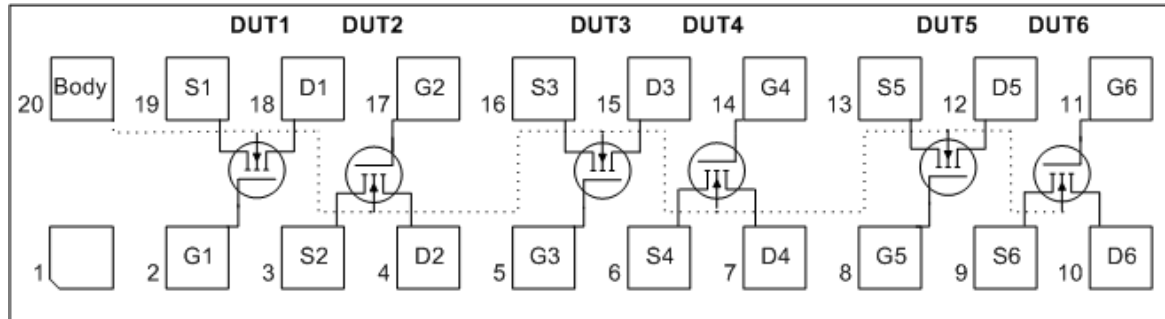


innovations  
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## 0,13 $\mu$ Teststruktur

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### S380: Low Voltage N-MOSFETs Common Body, Vertical Orientation



#### Vertical Hookup Information

Probe Pad Description	DUT1	DUT2	DUT3	DUT4	DUT5	DUT6
Common Body	20	20	20	20	20	20
GATPOLY Gate	2	17	5	14	8	11
Source	19	3	16	6	13	9
Drain	18	4	15	7	12	10

#### Module Rules

MR	Description	Value
1	Maximum Source / Drain Lead Width	5
2	Substrate / Body Lead Width	12
3	Minimum GATPOLY Space to ACTIV	0.1
4	Minimum GATPOLY Interconnect Width	3
5	Length of GATPOLY Extension	0.2
6	Width of GATPOLY Extension	0.13

#### Design Rules

DR	Description	DUT1	DUT2	DUT3	DUT4	DUT5	DUT6
1	GATPOLY Gate Width per Transistor	10	10	10	0.15	0.15	10
2	GATPOLY Gate Length	0.12	0.13	0.18	0.13	10	10
3	GATPOLY Overhang of ACTIV	0.18	0.18	0.18	0.18	0.18	0.18
4	Minimum ACTIV End Overlap of CONT	0.07	0.07	0.07	0.07	0.07	0.07
5	Minimum ACTIV Side Overlap of CONT	0.07	0.07	0.07	0.07	0.07	0.07
6	Source/Drain CONT Space to Gate	0.11	0.11	0.11	0.14	0.14	0.11
7	METAL1 Overlap of Source/Drain CONT	0.06	0.06	0.06	0.06	0.06	0.06
8	Source/Drain CONT Size X	0.16	0.16	0.16	0.16	0.16	0.16
9	Source/Drain CONT Size Y	0.16	0.16	0.16	0.16	0.16	0.16
10	Source/Drain CONT Spacing	0.18	0.18	0.18	0.18	0.18	0.18
11	Body Space to Source/Drain ACTIV	3.24	3.24	3.24	3.24	3.24	3.24
12	#of Proximity Gates per Side	2	2	2	2	2	2
13	Proximity Gate Space	0.38	0.38	0.38	0.44	0.44	0.38
14	# of Transistor Columns	1	1	1	1	1	1
15	# of Transistor Rows	1	1	1	1	1	1
16	Transistor Column ACTIV Spacing	0.21	0.21	0.21	0.21	0.21	0.21
17	Transistor Row ACTIV Spacing	0.21	0.21	0.21	0.21	0.21	0.21
18	GATPOLY Protection Capacitor Size	0	0	0	0	0	0
19	Gate Protection Diode Size	2.12	2.12	2.12	2.12	2.12	2.12
	# of Source/Drain CONT	29	29	29	1	1	29
	METAL1 Width over Source/Drain CONT	5	5	5	5	5	5
	Total # of Transistors	1	1	1	1	1	1
	Total Gate Width	10	10	10	0.15	0.15	10

